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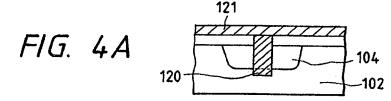
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(54) Electrode for semiconductor device and method for producing the same.

There is provided a semiconductor device with very small functional elements, which can be constructed by necessary minimum components without any unnecessary surface area, thus being capable of significantly reducing the layout area and adapted for achieving a fine geometry and a high level of integration. The semiconductor device is provided with a first semiconductor area of a first conductive type (for example a p⁻ well) and a second semiconductor area formed on or under the first semiconductor area and having a second conductive type different from the first conductive type (for example a source or drain area), in which an electrode electrically connected to the first semiconductor area is formed through the second semiconductor area, and the first and second semiconductor areas are shortcircuited by the above-mentioned electrode.



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EUROPEAN SEARCH REPORT

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EP 91 30 4828

DOCUMENTS CONSIDERED TO BE RELEVANT				
Category	Citation of document with of relevant p	indication, where appropriate, assages	Relevant to claim	CLASSIFICATION OF THE APPLICATION (Int. Cl.5)
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х	PATENT ABSTRACTS OF JAI vol. 10, no. 150 (E-40: & JP-A-61 008 969 (NIS January 1986 * abstract *	8)31 May 1986	1,2	
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The present scarch report has been drawn up for all claims				
Place of search THE HAGUE Date of completion of the search THE HAGUE 09 DECEMBER 1991		MTMO	Reminer DUN B.J.	
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CATEGORY OF CITED DOCUMENTS X: particularly relevant if taken alone Y: particularly relevant if combined with another document of the same category A: technological background O: non-written disclosure P: intermediate document A: member of the same patent family, corresponding document				

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